Sheet 1 of 11 FORM PTO-1449 INFORMATION DISCLOSS RESTATEMENT BY APPLICANT

(Modified)

U.S. Department of Commerce Patent and Trademark Office

Attorney Docket No NICHIA-00800 Serial No. 09 500288

Applicant Shuji Nakamura, et al

Group Art Unit.

	(37 CFR \$ 1.98(b	1)		Filing Date	February 8, 2000
				U.S. PATENT DOCUMENTS	
İ	Examiner	Serial Patent	Issue Date	Applicant Patentee	Class

Examiner Initials		Serial Patent Number		Issue Date	Applicant Patentee	Class	Subclass	Filing Date
Wil	AA	3566215	<i>></i>	2 23 71	Heywang	317	235	7 31 68
i	AB	3593191		7 13 71	Henker	331	94.5	9 24 69
	AC	3655439	>	4 11 72	Serter	117	212	6 16 69
	AD	3658585	y	4 25 72	Folkmann, et al.	117	201	2 26 70
	AE	3704427	V	11 28 72	Heywang	331	94 5	6/3/64
	AF	3705567	\checkmark	12 12 72	Emels	118	49	1 22 71
	AG	3737737	V	6 5 73	Heywang, et al.	317	234.R	10'6/71
	AH	3747559	v	7 24 73	Dietze	118	48	5 15/72
	AI	3793984	V	2 26 74	Kasper, et al.	118	48	11/13/72
	AJ	3819974	1	6 25 74	Stevenson, et al.	313	499	3/12/73
	AK	3853974	√	12 10 74	Reuschel, et al.	264	81	2/21/73
	AL	3941647	V	3 2 76	Druminski	156	612	3 8 73
	AM	3948693	V	4 6 76	Weyrich, et al	148	171	7 23 74
	AN	3963537	V	6 15 76	Kniepkamp, et al	148	175	8/27/74
	AO	3965347	V	6/22,76	Heywang	250	211.J	11/12/74
	AP	3974561	V	8 17.76	Schnoeller	29	611	5/30/74
	ΑQ	4020791	√	5 3 777	Reuschel, et al	118	49 1	11/19/74
	AR	4062035	/	12/6/77	Winstel	357	17	1/28/77
	AS	4098223	V	7:4/78	Ertl, et al.	118	48	11/4/76
	AT	4102298	\checkmark	7 25 78	Dietze, et al	118	.5	6.10 76
	AU	4108539	V	8 22/78	Gort, et al	350	201	11/18/76
	AV	4113381	/	9-12.78	Epstein	356	5	11-18-76
	AW	4133702	V	1 9 79	Krimmel	148	1.5	8 11 77
	AX	4140546	/	2 20 79	Krimmel	148	1.5	8 17 '77
	AY	4154625	/	51579	Golovchenko et al.	148	1.5	11/16/77
	AZ	4170018	V	10-2-79	Runge	357	17	3/30/78
	BA	4261770	/	4 14 81	Splittgerber, et al	148	171	3 13 80
	ВВ	4351695	/	9 28 82	Hieber, et al	156	603	1 2 81
	вс	4404265	V	9 13 83	Manasevit	428	689	4 7 78
	F.	4410993	/	10 18 83	Zschauer	372	44	4 17 81
	PE	4423349	/	12 27 83	Nakajima, et al	313	487	7.1.81
	FF	4505765	√	3 19 85	Irommer	148	171	6 17 83
V	ħG	4521448	/	6 4 85	Sasakı	427	88	3 3 83

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Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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ORM P10)-1449	May 2 2 200	چ (وی)ر	U.S. Depar	tment of Commerce	Attorney Docket No	NICHIA-00800	Serial No 0	9 500288
(lodified)		F. 100	10 (6) 44	Patent and	l Trademark Office	Applicant Shuji Nak	amura, et al		
IN T CER \$ 1		IO PISCLOSUR	ERYAT	FEMENT BY A	APPLICANT	Filing Date February	. 8, 2000	Group Art U	nit
	БН	4531142	/	7 23 85	Weyrich, et al		357	17	2 16 83
120	BI	4568206	/	2 4 86	Imazaike		384	530	12 3 84
	BJ.	4596998	<i>V</i>	6 24 86	Krimmel		357	17	7 19 84
+	BF		7	7 8 86	Falckenberg, et al		427	74	9 12 84
-	BL	4599245	/	7 8 86	Falckenberg, et al	<u> </u>	427	74	9 11 84
_	BM	4604637	/	8 5 86	Ruhle, et al.		357	17	3 1 83
+	BN	4615766		10 7 86	Jackson, et al.		156	662	2 27 85
-	BC		X	4 7 87	Amann, et al		372	50	12 23 85
+	BP	4661175	/	4 28 87	Kuphal, et al.		148	171	6 6 85
	BQ		✓ √	6.2.87	Maerz, et al.		156	649	4/21/86
+	BR		1	7 21 87	Amann		372	44	9.13-85
	BS	4683574	./	7.28′87	Heinen		372	44	9 12/85
+	вт	4722088	./	1/26/88	Wolf	·	372	44	9/6/85
 -	BU	4740259	/	4/26/88	Heinen	<u> </u>	156	234	9/15/86
+	BV	4742525		5/3/88	Heinen, et al.		372	44	9/6/85
	BW	4744088	V/	5 10 88	Heinen, et al.		372	50	3/13/87
	BX	4746195	<u>/</u>	5/24/88	Auracher, et al		350	320	3/13/85
+	BY	4763979	//	8-16-88	Heywang		350	96.20	9/23/86
1	BZ	4768199	<u>/</u>	8/30/88	Heinen, et al.		372	36	9/5/86
-	CA	4792200	/	12/20 88	Amann, et al.		350	96.12	4/1/87
+	СВ	-	/	12.20 88	Mueller, et al.		372	46	1/30/87
-	cc			4/4/89	Heinen		437	129	5/26/87
-	CD			5 9 89	Shinomiya, et al.		250	483.1	10 1/87
1	CE	4835575	./	5,30.89	Plihal		357	30	2/3/88
	CF		/	6 20 89	Heinen		357	17	12.7/87
+	CG	4845723	./	7 4 89	Heinen, et al.		372	38	2/22/88
-	СН	4855118		8 8 89	Ichinose, et al		423	301	4/12/88
+	CI		> +	8 22 89	Minematu, et al.		313	487	3/2 88
-	CJ	4864369	1	9:5:89	Snyder, et al.		357	17	7/5/88
-	CK	4869568	X	9 26 89	Schimpe		350	96.12	9 29 88
	32	4890033		12 26 89	Ichinomiya, et al		313	487	6 28 88
1	CM	4904617	<u> </u>	2 27 90	Muschke		437	129	8 25 88
1	23	4904618	7	2 27 90	Neumark		437	150	8 22 88
+	12	4907044		3 6 90	Schellhom, et al		357	17	7 14 89
-	35	4907534	了 フ	3 13 90	Huang, et al		118	725	12 9 88
\forall	70	4911102		3 27 90	Manabe, et al		118	719	1 26 88

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Sheet 3 of 11 FORM PTO-1449 (Modified)

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Attorney Docket No. NICHIA-00800 Serial No.09 500288 Applicanti Shuji Nakamura, et al.

INFORMATION DISCLOSIVE STATEMENT BY APPLICANT

Filing Date | February 8, 2000 Group Art Unit (37 CFR § 1.98(b))

Wil	CP	4918497	4 17 90	Edmond	357	17	12 14 88
	CS .	4929907	5 29 90	Berkel	330	252	3 8 89
	CT	4944837	7 31 90	Nishikawa, et al.	156	646	2 28 89
	cu	4945394	7 31 90	Palmour, et al	357	34	10 26 87
	cv	4946547	8 7 90	Palmour, et al	156	643	10 13 89
1	CW	4947218	8 7 90	Edmond, et al	357	13	11 3 87
	СХ	4959174	9 25 90	Nakajima, et al	252	301.6R	3/16/89
	CY	4960728	10 2 90	Schaake, et al.	437	82	10-11/88
	CZ	4966862	10 30 90	Edmond	437	100	8 28 89
	DA	4971739	11 20 90	Ichinose, et al.	264	61	4/12/89
	DB	4977567 \	/	Hanke	372	45	10/11/89
	DC	4982314	17191	Miki	363	16	12 4 89
	DD	4985742	1 15 91	Pankove	357	34	7.7 89
	DE	4987576	1 22 91	Heinen	372	46	11/3/89
	DF	4990466	2′5′91	Shieh, et al	437	129	11/1/88
	DG	4990990	2 5 91	Albrecht, et al.	357	30	3/23/88
	DH	5005057	4 2 91	Izumiya, et al	357	17	4/13/90
	DI	5006908	4/9 91	Matsuoka, et al.	357	17	2/12/90
	DJ	5008735	4 16/91	Edmond, et al.	357	74	12/7/89
	DK	5008789	4 16 91	Arai, et al.	362	255	2/14/90
	DL	5019746	5 28 91	Merg	313	512	12:4:89
	DM	5023686	/ 6/11/91	Helmut, et al.	357	30	6/15/90
	DII	5027168	6 25 91	Edmond	357	17	8.28 89
	DO	5034956	7 23 91	Gessner. et al	372	45	11 2 89
1	DP	5041334	8 20 91	Nakajima, et al.	428	407	12-19-89
	DQ	5042043	8/20/91	Hatano, et al.	372	45	4/13/90
	DR	5045896	9 3 91	Ash, et al.	357	17	3 21 89
	DS	5049779 V	7	Itsuki, et al	313	486	4/28/89
	DT	5061972 V	10.29.91	Edmond	357	13	9/13/90
	מם	5065207	11 12 91	Heinen	357	30	2 5 91
	SV	5077145	12 31 91	Shinomiya, et al	428	691	12 21 90
	L'A	5093576	3 3 92	Edmond, et al	250	370 01	3 15 91
	7x	5119540	6 9 92	Kong, et al	29	25 01	7 24 90
	ΣΥ	5120619	6 9 92	Nakajima, et al	428	690	11 7 90
	153	5122845	6 16 92	Manabe, et al	357	17	2 26 90
V	EA	5128955	7 92	Danielmeyer	372	94	8 18 88

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FORM PTO-1449

(Modified)

U.S. Department of Commerce Patent and Trademark Office Attorney Docket No. NICHIA-00800 Serial No. 09 500288

Applicant Shuji Nakamura, et al.

INFORMATION DISCEMBERE STATEMENT BY APPLICANT

(37 CFR § 1.98(b)) Filing Date: February 8, 2000 Group Art Unit

T CFR § 1	98(b))							
لالها	EB	5146465		9 8 92	Khan, et al.	372	45	2 1 91
1	EC	5155062	V	10 13 92	Coleman	437	100	12 20 90
	ED	5171370		12 15 92	Reithmaier, et al	118	726	4 18 90
	EE	5182670	V	1 26 93	Khan, et al.	359	359	8,30,91
1	EF	5184247		2 2 93	Schimpe	359	344	7 17 90
	EG	5185207	V	2 9 93	Furuoka, et al.	428	404	12 27 91
	ЕН	5200022	1	4 6 93	Kong, et al	156	612	10 3 90
	EI	5202777	/	4 13 93	Sluzky, et al.	359	50	4/1/92
	ΕĴ	5205905	7	4 27 93	Kotaki, et al.	156	662	5/30 91
	EK	5208878		5 4 93	Thulke	385	14	10/2/91
	EL	5210051	·	5'11'93	Carter, Jr.	437	107	6′5′91
1	EM	5218216		6.8.93	Manabe, et al.	257	103	12/20/91
	EN	5229626	×	7 20 93	Ebitani, et al.	257	84	3/27.92
<u> </u>	EO	5233204	V	8'3'93	Fletcher, et al.	257	13	1/10 92
1	EP	5239188	<u> </u>	8′24′93	Takeuchi, et al	257	76	11/4/92
	EQ	5247533		9'21/93	Okazaki, et al.	372	45	12/26/91
	ER	5250366	<i>\</i>	10.5 93	Nakajima, et al.	428	690	5/8/92
	ES	5252499		10/12/93	Rothschild	437	22	8/15/88
1	ET	5252839	1	10 12 93	Fouquet	257	13	6/10/92
	EU	5260960	- \ /	11/9 93	Amann, et al	372	46	4/23/92
1	EV	5264713		11/23/93	Palmour	257	77	6/14/91
†	EW	5266503	./	11 30 93	Wang, et al.	437	24	10/2/91
	EX	5270554	-V_/	12 14 93	Palmour	257	77	6.14/91
1	EY	5272108	y /	12'21'93	Kozawa	437	127	2/26.92
	EZ	5278433	V	1/11/94	Manabe, et al.	257	103	8/7/92
	FA	5281830	$\sqrt{}$	1/25/94	Kotaki, et al	257	86	10/24/91
	FB	5290393		3 1/94	Nakamura	156	613	1/28/92
	FC	5306662	<i>\tag{\tau}</i>	4 26 94	Nakamura, et al.	437	107	11/2 92
	FD	5312560	V	5/17/94	Somatomo, et al.	252	301.4 S	3/18/93
	FE	5323022	V.	6 21 94	Glass, et al.	257	77	9-10/92
	FF	5330791		7 19 94	Aihara, et al	427	215	4 16 93
1	F 3	5334277		8 2 94	Nakamura	117	102	10 22 91
	FH	5336080		8 9 94	Sumitomo, et al	428	407	12 17 92
+-	FI.	5338944		8 16 94	Edmond, et al	257	76	9 22 93
_	183	5341390	<u> </u>	8 23 94	Yamada, et al	372	45	4 15 93
1/	FF	5343316		8 30 94	Morimoto, et al	359	50	6 29 93

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Date Considered 6/2-1/0

(RM PTC odified))-1449	MAY 2	² 2000	US Depo Patent ar ty	artment of Commerce and Trademark Office	Attorney Docket No N		Serial No (9 500288
18	FORMA	TIE DISCLO	SURE Ş	EXTEMENT BY:	APPLICANT	Applicant Shuji Nakami	ıra, et al.		
7 CFR \$ 1		TRADE	ABK DI			Filing Date: February 8,	2000	Group Art Unit.	
W>L	FL	5344791	1	9 6 94	Huang		437	126	8 14.92
1	FM	5359345	/	10 25 94	Hunter		345	102	8 5 92
	FN	5363390	V	11 8 94	Yang, et al.		372	22	11 22.93
	FC	5366834	V	11 22 94	Yoneda, et al.		430	23	5 5.93
	FP	5369289	V	11 29 94	Tamaki, et al.		257	99	10/30/92
	FQ	5376303	/	12 27.94	Royce, et al.		252	301.4 R	1/10-94
	FR	5376580		12-27-94	Kish, et al.		437	127	3/19/93
	FS	5381103	V	1 10 95	Edmond, et al.		324	753	10/13/92
	FT	5382822	V.	1/17/95	Stein		257	410	9/27/93
	FU	5389571		2/14/95	Takeuchi, et al.		437	133	4/16/93
	FV	5390210	V	2.14/95	Fouquet, et al.		372	92	11/22/93
	FW	5393993	V	2/28/95	Edmond, et al.		257	77	12/13/93
	FX	5394005	/	2/28/95	Brown, et al.		257	461	2/18/94
	FY	5403774	V	4/4/95	Shieh, et al.		137	129	11/6/92
	FZ	5404282	V	4/4/95	Klinke, et al.		362	249	8/19/94
	GA	5408120	V.	4/18/95	Manabe, et al.		257	431	1/22/93
	GB	5409859		4 25/95	Glass, et al.		137	187	4/22/94
	GC	5416342		5/16/95	Edmond, et al.		257	76	6/23/93
	GD	5417886	V	5/23/95	Tateiwa, et al.		252	301.4 R	9/20/93
	GE	5433169	V	7/18/95	Nakamura	1	17	102	4/6/94
	GF	5433533	/	7/18/95	lmazaike	3	84	488	12/20/93
	GG	5433888	V	7/18/95	Okada, et al.	2	52	301.4 R	9/20/93
	GH	5435938	V	7/25/95	Bando, et al.	2	52	301.4 S	3/10/94
	GI	5438198	V.	8/1/95	Ebitani, et al.		50	330	5/3/94
	GJ	5459107	1	10/17/95	Palmour		37	238	6/5/92
	GK	5465249		11/7/95	Cooper, Jr. et al.		65	149	11/26/91
	GL	5467291	V	11/14/95	Fan, et al.		64	578	12/5/91
	GM	5468678	√.	11 21 95	Nakamura, et al.		37	107	1/12/94
	GN	5475241		12/12/95	Harrah, et al.		57	99	10/27/93
	GC	5497012		3 5 96	Moll		57	183	6/15/94
	GP	5502316	7	3 26 96	Kish, et al	25		94	10/12/95
	32	5506421	/	4 9 96	Palmour	25		77	11/24/92
	GP .	5511084	V	4 23 96	Amann	33		20	1 17-95
	93	5514627	7	5 7 96	l owery, et al	43		209	1 24 94
	GT	5523018	V	6 4 96	Okada, et al	25		301.4 P	3 23 95
V	GU.	5523589	7	6 4 96	Edmond, et al	25		77	9 20 94
nner		age				Date Consid		1.1	7 20 74

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	SFORMAT	DISCLOSUI	RE ST.	ATEMENT BY A	PPLICANT	Filing Date February		Group Art U	init:
	1 98(b))	5539217	7	7 23 96	Edmond, et al.		257	77	8 9 93
<u> نخا</u>	GW	5563422	7	10 8 96	Nakamura, et al		257	13	4 28 94
}_	GX	5578839	./	11 26 96	Nakamura, et al	OPE	257	96	11 17 93
+-	GY	5583879	<u>/</u>	12 10 96	Yamazakı, et al.	01.	372	45	4'19 95
+	GE	5585648	/	12 17 96	Tischler	MAY 2 2 2000	257	77	2 3 95
+	HA	5587593	/	12 24 96		MAY Z Z ZOO	257	94	4 19 95
	нв	5592501	7	1 7 97	Edmond, et al.	MAI 2	372	45	9-20/94
-	нС	5592578		1 7.97	Ruh	RADE	385	31	11.1.95
	нр	5596595	V	1 21 97	Tan, et al.		372	96	6/8 95
+	HE	5604135	V	2 18 97	Edmond, et al.		437	22	8/12/94
+	HF	5604763	/	2/18/97	Kato, et al.		372	45	4/19/95
+	НG	5612260	Ž	3 18 97	Palmour		437	238	12/9 94
	нн	5614736		3 25 97	Neumann, et al.		257	102	9 25 95
+-	ні	5616177	<u>v</u>	4.1/97	Yamada		117	102	2/22 '95
	нЈ	5620557	/	4/15/97	Manabe, et al.		438	507	6/26/95
+	нк	5621749	V /	4 15 97	Baney		372	69	9 6 95
	HL	5625202	v	4 29 97	Chai		257	94	6.8 95
1	нм	5627244		5 6 97	Sato		526	92	4/26/95
†	HN	5629531		5 13 97	Palmour		257	77	12/9/94
	но	5631190		5 20 97	Negley	···	438	33	10/7/94
	НР	5635146	<u>,</u>	6 3 97	Singh, et al	, <u>, , , , , , , , , , , , , , , , , , </u>	423	65	11/30/95
1	НQ	5642375		6/24/97	King, et al.		372	97	10/26/95
1	HR	5650641	V	7:22 97	Sassa, et al.		257	88	8'31/95
	HS	5652434	/	7 29 97	Nakamura, et al.		257	13	6 17 96
	нт	5652438	V	7 29 97	Sassa, et al.		257	94	7/19 95
	нu	5656832	V	8 12/97	Ohba, et al.		257	190	3/8/95
	HV	5659568	/	8 19 97	Wang, et al		372	96	5/23.95
	HW	5661074	V	8 26 97	Tischler		438	32	5 24-95
	HX	5661316	V,	8 26 97	Kish, Jr., et al.		257	190	9 20/96
	HY	5661742		8 26 97	Huang, et al.		372	46	5,22 96
	нг	5670798	√ .	9 23 97	Schetzina		257	96	3 29 95
	IA	5679153	$\sqrt{.}$	10 21 97	Dmitney, et al		117	106	11 30 94
	IB	5684623	$\sqrt{}$	11 4 97	King, et al		359	346	11 21 96
	::	5686737	√,	11 11 97	Allen		257	77	9 16 94
1.	1:	5700713	$\sqrt{\ }$	12 23 97	Yamazaki, et al		437	129	3 20 95
Ψ^-	IE	5707139	$\sqrt{}$	1 13 98	Haitz		362	231	11 1 95
niner		Jan Ha	ン			Date (onsidered	6/21/01	

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INI	FORMAT	ioz preeros	URE ST	TEMENT BY A	APPLICANT				
7 CFR § 1		Agr.	EMBE			Filing Date Februar	y 8, 2000	Group Art U	nit
WSL	IF	5718760	7.	2 17 98	Carter, et al		117	84	2 5 96
	IG	5719409		2 17 98	Singh, et al.		257	77	6 6 96
	IH	5724062	<i>\'</i>	3 3 98	Hunter	ØE_	345	102	9 21 94
	ΙΙ	5724373		3 3 98	Chang /	71 - Jag	372	20	11-15-96
	IJ	5724376		3 3 98	Kish, Jr., et al.	MM 5 5 57000 77	372	96	11/30/95
	IK	5727014	V.	3 10 98	Wang, et al.		372	96	10 31 95
	IL	5729029		3 17 98	Rudaz 🗜	, A	257	13	9 6 96
	IM	5729567	X	3 17.98	Nakagawa	TETRADENT	372	99	4/25.96
	IN	5733796		3/31.98	Manabe, et al.		437	127	11/9/95
	IC	5734182	Ü	3 31 98	Nakamura, et al.		257	96	6.10 96
	ΙP	5739552		4 14 98	Kimura, et al.		257	89	10′24/95
	IQ	5739554		4:14/98	Edmond, et al.		257	103	5/8/95
	IR	5741431		4/21.98	Shih		216	65	5/15/97
_	IS	5741724		4 21 98	Ramdani, et al.		437	128	12/27 96
	IT	5742133		4 21 98	Wilhelm, et al.		315	291	9.9'96
1	IU	5747832		5/5,98	Nakamura, et al.		257	103	6/10/96
	IV	5753939		5 19 98	Sassa, et al.		257	94	3/7/97
	IW	5758951		6'2 98	Haitz		362	259	6/27/97
1	IX	5761229		6′2 98	Baldwin, et al.		372	31	1/25.96
	IY	5767581		6/16/98	Nakamura, et al.		257	749	6/17/96
 	ΙZ	5771254		6'23'98	Baldwin, et al.		372	31	6/3/96
-	JA	5776837		7'7/98	Palmour		438	767	11/19/96
1	JВ	5777350	./	7'7 98	Nakamura, et al.		257	96	11/30/95
 	JC	5777433	./	7 7 98	Lester, et al.		313	512	7/11/96
-	JD	5779924		7*14 98	Krames, et al.		216	24	3/22/96
	JE	5780120	V	7 14 98	Belouet, et al.		427	554	12/18/96
	JF	5785404		7 28 98	Wiese		362	32	6/29/95
	JG	5793054		8 11/98	Nido		257	18	6/13/96
	JH	5793062		8 11 98	Kish, Jr., et al.		257	98	10/24/97
	JI	5805624		9 8 98	Yang, et al		372	45	7 30 96
1	33	5808323	./	9 15 98	Spaeth, et al		257	88	3 29 96
	JF	5808592	7	9 15 98	Mizutani, et al		345	83	4 21 95
		5809050		9 15 98	Baldwm, et al		372	43	1 25 96
1	.M.	5811319	1/	9 22 98	Korke, et al		438	46	3 26 96
1	711	5811931	/	9 22 98	Mueller-Mach, et al		313	512	3 4 96
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	LB	5923118	6 13 99	Jennato, et al	313	485	3 7 97
	LC	5923690	7 13 99	Kume, et al	372	46	1 24 97
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1	MK	EP0380340A3	8 1 90	EP		H01L	29 91
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Ì	MM	EP0731512A2	9 11 96	EP EP	Š	HOIL	33 00
	MN	EP0731512A3	7 2 97	EP	WADEMARK OF	H011.	33 00
1	мо	EP0781619A1	7 2 97	EP	QUEIN	B2311	7.02
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		Number	Publication Date	Country	Patent Office	Class		Yes	No
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